



IFW

PATENT  
8007-1118

**IN THE U.S. PATENT AND TRADEMARK OFFICE**

Applicants: HOSOKAWA et al. Confirmation: 6310  
Serial No.: 10/594,567 Art Unit: Not assigned  
Filed: September 27, 2006 Examiner: Not assigned  
For: MATERIAL FOR CHEMICAL VAPOR DEPOSITION  
AND THIN FILM FORMING METHOD

**INFORMATION DISCLOSURE STATEMENT**

Assistant Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**December 27, 2006**

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, included with the attached Form PTO-1449 are references discussed in the present specification, which are hereby made of record in the above-identified application. An English language abstract is provided for each document. Together, the discussion in the specification and accompanying abstracts satisfy the requirement for a concise explanation of relevance.

This Information Disclosure Statement is being submitted within three months of the filing date of the present application; therefore, no fee is required. The Examiner is courteously requested to initial and return a copy of the accompanying Form PTO-1449 to confirm entry into the record and consideration of the listed references.

Respectfully submitted,

**YOUNG & THOMPSON**

BY:

Robert J. Patch  
Reg. No. 17,355

745 South 23<sup>rd</sup> Street  
Arlington, VA 22202  
703-521-2297 (telephone)  
703-685-0573 (telecopier I)  
703-979-4709 (telecopier II)

RJP:rk



## **ATION DISCLOSURE CITATION IN AN APPLICATION**

(Use several sheets if necessary)

DEC 27 2006

Attorney Docket No.:  
**8007-1118**

**Application No.:**  
**10/594,567**

Applicant:  
**HOSOKAWA et al.**

**Filing Date:**

Group Art Unit:  
**2812**

## **U.S. PATENT DOCUMENTS**

## **FOREIGN PATENT DOCUMENTS**

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

ANSWER

**EXAMINER:**

**DATE CONSIDERED**

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

\* English language abstract provided for the Examiner's convenience

RJP:rk